

MAINTAINING A REACTOR CHAMBER OF  
A CHEMICAL VAPOR DEPOSITION SYSTEM

ABSTRACT OF THE DISCLOSURE

5 Maintaining a reactor chamber of a chemical vapor  
deposition system includes depositing layers on an inner  
surface of the reactor chamber, where the layers form an  
accumulation layer. When the accumulation layer reaches a  
specified thickness, a plasma clean cycle is performed by  
introducing cleaning gas into the reactor chamber. The  
volume of the cleaning gas used during one or more plasma  
clean cycles is calculated, where the volume indicates  
10 the volume of cleaning gas introduced into the reactor  
chamber. A notification is provided when the volume of  
the cleaning gas used during the plasma clean cycles has  
reached a predetermined volume.